

# PATENT ABSTRACTS OF JAPAN

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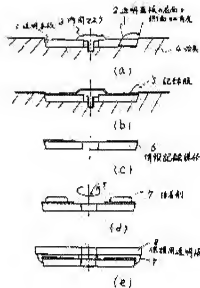
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## (54) MANUFACTURE OF INFORMATION RECORDING MEDIUM

(57)Abstract:

PURPOSE: To prevent moisture or the like from penetrating an information recording part by sticking the recording film of an information recording substrate and a protective transparent plate to each other with an adhesive and coating the recording film with the adhesive to isolate it from the outside atmosphere.

CONSTITUTION: The center hole of a transparent substrate 1 where an angle 2 formed between the bottom face and the side face is 90W135° is used to attach this transparent substrate 1 to a jig 4 having a recessed part, which has the same diameter as the transparent substrate 1 and has a depth equal to or deeper than the transparent substrate so that the transparent substrate is fitted to the recessed part, together with an inner peripheral mask 3, and this jig 4 is set to a sputtering device. A recording film 5 is formed by sputtering, and the substrate 1 is detached from the jig 4 to obtain an information recording substrate 6. This substrate 6 is coated with an adhesive 7 while being rotated in the direction of an arrow 9, and a protective transparent plate 8 slightly larger than the information recording substrate 6 is put on the substrate 6 in vacuum, and the air pressure is restored to stick the plate 8. Thus, impurities, especially, moisture in the outside atmosphere is prevented from penetrating the information recording part.



## LEGAL STATUS

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